L Number		Search Text	DB	Time stamp
6	9		USPAT;	2004/02/18 14:4
	1	("6291130") or ("5856561")).PN.	US-PGPUB/	
			EPO; JPO;	
	1		DERWENT	
	1	("20020150834").PN.	USPAT;	2003/06/10 15:2
			US-PGPUB;	
			EPO; JPO;	
	3086104	and the Adiaban and	DERWENT	1
	2088104	resin binder polymer resist photoresist	USPAT;	2003/06/10 15:2
			US-PGPUB;	I .
			EPO; JPO;	
	15856	(photoscid scid (photo adj scid)) near	DERMENT USPAT:	
	23030	denerats3	US-PGPUB;	2003/06/10 15:2
		generacys	EPO: JPO:	
			DERNENT	1
	2055	acetal near moiety) (acetal near compound	USPAT:	2003/06/11 08:5
		deces near sorter) (deces near compound	US-PGPUB	2003/06/11 08:5
			EPO: JPO:	
			DERNENT	i
	197	(resin binder polymer resist photoresist)	USPAT;	2003/06/11 10:4
		and ((photoacid acid (photo adj acid)) near .	US-PGPUB:	2003/06/11 10:4
		generat93) and (acetal near noiety) (acetal	EPO: JPO:	
		near compound)	DERWENT	
	275472		USPAT	2003/06/10 15:3
	275412	delylate machinelylate cyclodictin	US-PGPUB;	2003/06/10 15:3
			EPO; JPO;	1
1			DERMENT	
	24	(2-methyladamantyl adj methacrylate)	USPAT;	2003/06/10 15:3
		(2-methyl adj adamantyl adj methacrylate)	US-PGPUB:	2003/06/10 1513
		is sectify out administry, and inclinativeness	EPO: JPO:	1
			DERMENT	1
i	16008	gamma-butyrolactone \$6butyrolactone	USPAT;	2004/02/09 11:1
		butyrolactone "gamma"-butyrolactone	US-PGPUB:	2004/02/09 11:1
		www.yeowoconto guino Dacytozactone	EPO; JPO;	
			DERWENT	
	146	(acrylate methacrylate cycloclefin ) and	USPATI	2003/06/10 15:3
1		((resin binder polymer resist photoresist)	US-PGPUB:	2003/06/10 15:3
		and ((photoscid scid (photo ad) acid)) near	EPO: JPO:	
		generat\$3) and (acetal near mojety) (acetal	DERWENT	1
		near compound) }	Distribute.	1
- 1	24	(S3-methyladamentyl sdj methacrylate)	USPAT:	2004/02/09 11:1
		(\$3-methyl adj adamantyl adj methacrylate)	US-PGPUB;	,,
		, ,,,,	BPO: JPO:	1
			DERMENT	
	24	(\$3-methyladamentyl adj methacrylate)	USPAT:	2003/06/11 15:1
		(\$3-methyl adj adamantyl adj methacrylate)	US-PGPUB)	
			EPO; JPO;	
			DERMENT	
	24	((2-methyladamantyl adj methacrylate)	USPATI	2003/06/11 15:2
		(2-methyl adi adamantyl adi methacrylate) )	US-PGPUB:	
		((S3-methyladamantvl adi methacrylate)	EPO; JPO;	
		(\$3-methyl adj adamsntyl adj methacrylate) )	DERWENT	
		((S3-methyladamantyl adj methacrylate)		
		(\$3-methyl adj adamantyl adj methacrylate)		
		)		
	14	(1(2-methyladamantyl adm methacrylate)	USPAT;	2003/06/11 15:2
		(2-methyl adj adamantyl adj methacrylate) )	US-PGPUB;	
		(((2-methyladamentyl adm methacrylate)	EPO: JPO:	
		(2-methyl adj adamantyl adj methacrylate) }	DERWENT	
		((\$3-methyladamantyl adj methacrylate)		
- 1		(\$3-methyl adj adamantyl adj methacrylate) )		
		((\$3-methyladamantyl adj methacrylate)		
		(\$3-methyl adj adamantyl adj methacrylate)		
		))) and (gamma-butyrolactone Sébutyrolactone		
		butyrolactone "gamma"-butyrolactone)		

	4	(([(2-methyladamantyl adj methacrylate)	USPAT:	2003/06/10 15:4:
		(2-methyl adj adamantyl adj methacrylate) )	US-PGPUB)	2003/00/10 13:4.
		(((2-methyladamantyl adi methacrylate)	EPO: JPO:	
		(2-methyl adj adamantyl adj methacrylate) )	DERNENT	
		((S3-methyladomantyl adi methacrylate)	Date Contract of	1
	i	(\$3-methyl adj adamantyl adj methacrylate) )		
		((S3-methyladamantyl adj methacrylate)		1
		(\$3-methyl adj adamantyl adj methacrylate)		
		))) and (gamma-butyrolactone \$6butyrolactone		
		butyrolactone 'gamma"-butyrolactone) ) and		
		((acrylate methacrylate cycloolefin ) and	1	
		((resin binder polymer resist photoresist)	1	1
		and ((photoacid acid (photo ad) acid)) near		1
		generat\$3) and (acetal near molety) (acetal		
		near compound())		
	4	((((2-methyladamantyl adj methacrylate)	USPAT:	2003/06/10 15:4:
		(2-methyl adj adamantyl adj methacrylate)	US-PGPUB:	2003/06/10 15:4.
		(((2-methyladamentyl adj methacrylate)		1
		(2-methyl adj adamantyl adj methacrylate)	EPO; JPO; DERMENT	
		((S3-methyladamantyl adj methacrylate)	DESWENT	1
		(\$3-methyl adj adamantyl adj methacrylate)		1
		((\$3-methyladamantyl adj methacrylate)		
		(\$3-methyl adi adamantyl adi methacrylate)		
		(53-methyl ad) edamantyl ad) methacrylate)  ))) and (gamma-butyrolactone \$6butyrolactone		
		butyrolactone "gamma"-butyrolactone)   and	1	1
		((resin binder polymer resist photoresist)		
		and ((photoscid scid (photo adj scid)) near generatS3) and (acetal near moiety) (acetal		
		generates) and (acetal near molety) (acetal		
		((((2-methyladamantyl adv methacrylate)	monam	2004/00/00 44 44
		(2-methyl adj adamantyl adj methacrylate)	USPAT;	2004/02/09 11:15
			US-PGFUB;	1
		(((2-methyladamantyl adj methacrylate)	EPO; JPO;	1
		(2-methyl adj adamantyl adj methacrylate) )	DERWENT	
		((\$3-methyladamantyl adj methacrylate)		1
		(\$3-methyl adj adamentyl adj methacrylate) )		
		((\$3-methyludamantyl adj methacrylate)		
		(\$3-methyl adj adamantyl adj methacrylate)		
		))) and (gamma-butyrolactone \$6butyrolactone	l	
		butyrolactone "gamma"-butyrolactone) ) and	1	1
		((scrylate methacrylate cycloolefin ) and		i
		((resin binder polymer resist photoresist)		1
		and ((photoacid acid (photo adj acid)) near		
		generat93) and (acetal near molety) (acetal		
		near compound)))) (((((2-methyladamantyl adj	1	
		methacrylate) (2-methyl adj adamantyl adj	1	
		methacrylate) ) (((2-methyladamantyl adj	1	1
		methacrylate) (2-methyl adj adamantyl adj		1
		methacrylate) ) ((\$3-methyladamantyl adj		1
		mothacrylate) (\$3-methyl adj adamsntyl adj		
		methacrylate) ) ((S3-methyladamantyl adj		
		methacrylate) (\$3-methyl adi adamantyl adi		
		methacrylate) ))) and (gamma-butyrolactone	1	
		Sébutyrolactone butyrolactone	1	1
		"gamma"-butyrolactone) ) and ((resin binder		i
		polymer resist photoresist) and ((photoacid		1
		acid (photo edj ecid)) near generat\$3) and		1
		(acctal near moiety) (acctal near		
1		compound()))		
i	20	(("2003082926") or ("2002150834") or	USPAT;	2003/06/10 16:23
		("2002081523") or ("6548221") or	US-PGPUB:	2000,00,10 10.2
		("2000482359") or ("2002051933") or	EPO: JPO:	
		("6492091") or (*2002102491") or (*6383713*)	DEBMENT	

	24		USPAT:	12003/06/10 16:23
		(*2002081523*) or (*6548221*) or	US-PGPUB:	
		(*2000482359*) or (*2002051933*) or	EPO; JPO;	
	1	("6492091") or ("2002102491") or ("6383713")	DERWENT	1
	1	or ("6348297") or ("6239231")).PN.)		
	1	((((((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate))		
		(2-methyl adj adamantyl adj methacrylate) )		1
		(((2-methyladamentyl adj methacrylate)		1
		(2-methyl adj adamantyl adj methacrylate) )		i .
		((\$3-methyladamantyl adj methacrylate)		1
	1	(\$3-methyl adj adamantyl adj methacrylate) ) ((\$3-methyladamantyl adj methacrylate)		
	İ	(\$3-methyl adj adamantyl adj methacrylate)		
		))) and (gamma-butyrolactone \$6butyrolactone		
		butyrolactone "gamma"-butyrolactone) ) and		
		((acrylate methacrylate cycloplefin ) and		
		((resin binder polymer resist photoresist)		1
	!	and ((photoscid acid (photo add scid)) near		
		generat\$31 and (acetal near moiety) (acetal		
		near compound())) (((((2-nethyladamantyl adj		
		methacrylate) (2-methyl adj adamantyl adj		
		methacrylate) ) (((2-methyladamantyl adj		
	1	methacrylate) (2-methyl adj adamantyl adj methacrylate) ) ((83-methyladamantyl adj		1
	1	methacrylate) (\$3-methy) add adamantyl add		
		methacrylate) ) ((S3-methyladamantyl adj		
		methacrylate) (\$3-methyl adm adamantyl adm		
		methacrylate) ))) and (gamma-butyrolactone		i
	1	\$6butyrolactone butyrolactone		
		"gamma"-butyrolactone) ) and ((resin binder	1	
		polymer resist photoresist) and ((photoacid	İ	
		acid (photo adj acid)) near generat\$3) and		
		(acetal near moiety) (acetal near compound)))))		
	2056	acetal near moiety) (acetal near compound	USPAT:	2003/06/11 09:05
		was nous source); (account near compound	US-PGPUB:	2003/00/11 03:03
			EPO; JPO:	
			DERWENT	
-	2055	acetal near molety) (acetal near compound	USPAT;	2003/06/11 09:37
			US-PGPUB;	
			EPO; JPO;	
	1377		DERWENT	
	1377	YAMAMOTO-HAJIME YAMAMOTO-HAJIME-C-O-CANON-KABU	USPAT; US-PGPUR:	2004/02/16 17:50
		YAMAMOTO-BAJIME-C-O-CANON-KASU	EPO: JPO:	
		YAMAMOTO-HAJIMU MURAKANI-KENICHI	DERMENT	
		MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU	DERMANI	
		TAKECHI-SATOSHI		
		TAKECHI-SATOSHI-C-0-FUJITSU-LI		
	2	(yAMAMOTO-HAJIME	USPAT;	2003/06/11 10:03
		YAMAMOTO-HAJIME-C-O-CANON-KABU	US-PGPUB;	
		YAMAMOTO-HAJIME-C-O-CANON-K-K	EPO; JPO;	
		YAMAMOTO-HAJIMU MURAKAMI-KENICHI	DERNENT	
		MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU TAKECHI-SATOSHI		
		TAKECHI-SATOSHI-C-O-FUJITSU-LI) and (acetal		l
		near moiety) (acetal near compound)		
	0	20020150834.URPN.	USPAT	2003/06/11 10:03
	44	(YAMAMOTO-HAJINE	USPAT:	2003/06/11 11:15
		YAMAMOTO-HAJIME-C-O-CANON-KABU	US-POPUB:	
		YAMAMOTO-HAJIME-C-O-CANON-K-K	EPO: JPO:	
		YAMAMOTO-HAJIMU MURAKAMI-KENICHI	DERWENT	
		MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU		1
		TAKECHI-SATOSHI		1
		TAKECHI-SATOSHI-C-O-PUJITSU-LI) and		
		(photoresist resist) and (\$Sacid near generat\$3)		
	6	(US-6517991-S or US-6291130-S or	USPAT:	2003/06/11 10:04
		US-6548221-S).did. or (US-20020150834-\$ or	US-PGPUB:	2003/08/11 10:04
		US-20030044718-\$).did. or	JPO	

	1 42	T / consumo to view			
	43	( (yAMANCTO-BAJIME YAMANCTO-HAJIME-C-O-CANON-KABU YAMANCTO-HAJIME-C-O-CANON-K-K YAMANCTO-BAJIME MURAKAMI-KENICHI MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU	USPAT; US-PGPUB; EPO; JPO; DERNENT	2003/06/11 10	):09
		TAKECHI-SATOSHI TAKECHI-SATOSHI-C-O-FUJITSU-LI) and (photoresist resist) and (\$5acid near generats3)) not ((US-6517991-8 or			
		US-6291130-\$ or US-6548221-\$).did. or (US-20020150834-\$ or US-20030044718-\$).did. or (UF-2002311587-\$).did.)			
	18633	(acetal) same (additive (dissolution adj inhibitor) compound)	USPAT; US-PGPUB; EPO; JPO; DERHENT	2003/06/11 10	):43
	5	((doctal) same (additive (dissolution adj inhibitor) compound) and (((yMAMACTO-HAJIME YANAMATO-HAJIME-CO-CANON-KABU YANAMATO-HAJIME-CO-CANON-K-K YANAMATO-HAJIME MERAMAT-KENICH	USPAT; US-PGPUB; EPO; JPO; DERNENT	2003/06/11 10	1:46
		NUBREAUT-KENICHIED NUBREAUT-KENICHIEDCU TARKEHL-SANTOSHI - CO-FRUITSU-LI] and (photoresis resist) and (\$\$8xcid near generat83)) not ([US-6517991-8 or US-6291130-6 or US-6584221-8), did. or (US-20020150814-8 or US-20030044718-\$), did. or (US-20020150814-8 or US-20030044718-\$), did.			
-	1477	lactone same acetal	USPAT; US-PGPUB; EPO; JPO; DERNENT	2003/06/11 10	1:48
	444	((acctal) same (additive (dissolution adj inhibitor) compound() and (photoresist resist) and (\$5acid near generat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 12	:35
	1	di-t-butoxyacetyl adj bisphenol adj "A"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 12	:36
		(acid adj (labile cleavable cleve dissociable)) (acid mear elminat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15	:09
		acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf	USPAT; US-PGPUB; EPO; JPO; DERNENT	2003/06/11 15	:26
	2482	[(acid adj (labile cleavable cleve dissociable)] (acid near elminat\$4)) and (acetal ketal (\$Serhoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15	:26
-	564	({(acid ad) (labile cleavable cleve dissociable) (acid near elemints)) and (acetal ketal (55ethoxy5sethoxy) tetrahydroturanyl tetrahydropyranyl thp thf )) and (430/270.1.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERMENT	2003/06/11 15	:41
-	14	((2-methy) adj methacrylate) ((2-methy) adj admantyl adj methacrylate) ((2-methy) adj admantyl adj methacrylate) ((2-methy) adj admantyl adj methacrylate) ((2-methy) adj admantyl adj methacrylate) (3-methy) adj admantyl adj methacrylate) (33-methy) adj admantyl adj methacrylate) bityrolateme memme i browne Shoutyrolateme	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15	:28

-	1 7	((((acid ad) (labile cleavable cleve	USPAT	
	1 '	dissociable)) (acid near clminat34)) and	USPAT; US-PGPHH:	2003/06/11 15:2
	1	(acctal ketal (\$5ethoxy\$5ethoxy)	EPO; JPO;	
		tetrahydrofuranyl tetrahydropyranyl thp thf	DERWENT	
		((((2-methyladamantyl adj methacrylate)	1	
	1	(2-methyl adj adamantyl adj methacrylate)	1	
		(((2-methyladamantyl adj methacrylate)		1
		(2-methyl adj adamantyl adj methacrylate)		
				1
	i	(\$3-methyl adj adamantyl adj methacrylate) ) ((\$3-methyladamantyl adj methacrylate)	1	
		(63-methyl adj adsmantyl adj methacrylate)		
		))) and (gamma-butyrolactone \$6butyrolactone		
	1	butyrolactone "gamma"-butyrolactone) )		
-	0	20030073030.URPN.	USPAT	2003/06/11 15:30
	14718	S5acid near generat83	USPAT;	2003/06/11 15:40
	1		US-PGPUB;	
			EPO; JPO; DERNENT	
	485	((((acid ad) (labile cleavable cleve	USPAT:	2003/06/11 15:40
		dissociable)) (acid near elminat34)) and	US-PGPUB;	2003/00/11 13.40
	1	(acetal ketal (\$5ethoxy\$Sethoxy)	EPO; JPO;	
	1	tetrahydrofuranyl tetrahydropyranyl thp thf )) and (430/270.1.ccls.)) and (\$5acid near	DERWENT	
		generat\$3)		
	484790	acrylic acrylate methacrylate methacrylic	USPAT:	2003/06/11 15:41
			US-PGPUB;	
	1		EPO; JPO;	
	426	((((acid adj (labile cleavable cleve	DERWENT USPAT:	
	1	dissociable)) (acid near elminats41) and	US-PGPUB:	2003/06/11 15:41
		(acetal ketal (SSethoxySSethovy)	EPO: JPO:	
		tetrahydrofuranyl tetrahydropyranyl thp thf	DERWENT	
		1) and (430/270 1.ccls.)) and (\$5acid near generat\$3)) and (acrylic acrylate	i	1
		methacrylate methacrylic)		
	253	"153" and (430/270.1.ccls.)	USPAT:	2003/06/11 15:41
			US-PGPUB:	2002/00/11 23/41
	1		EPO; JPO;	
	420	(((((acid adj (labile cleavable cleve	DERWENT	
	140	dissociable)) (acid near elminatS4)) and	USPAT; US-PGPUB;	2003/06/11 15:44
		(acetal ketal (SScthoxySSethoxy)	BPO: JPO:	
		tetrahydrofuranyl tetrahydronuranyl sho she	DERHENT	
		)) and (430/270.1.ccls.)) and (\$5acid near		
		generat(3)) and (acrylic acrylate methacrylate methacrylic)) and		
		(430/270.1.ccls.) and		
	373	((((((acid adj (labile cleavable cleve	USPAT:	2003/06/11 15:48
		dissociable)) (acid near elminat\$4)) and	US-PGPUB;	2003/00/11 15:48
		(acetal ketal (\$5ethoxySSethoxy)	EPO: JPO:	
		tetrahydrofuranyl tetrahydropyranyl thp thf	DERWENT	
	1	)) and (430/270 1.ccls.)) and (\$5scid mear generat\$3)) and (acrylic scrylate		1
		methacrylate methacrylic)) and		
		(430/270.1.ccls.)) and ((resist binder		
		photoresist resin) near composition)		

(labile cleavable cleve	367 [[[[[[[[acid	
cid most cintins(4)) and cid most cintins(4)) and (1 cintins)	dissociabile, in extendador de la contracta de	
hf	Secid more cinitati(4)  and	diamocialia) [seld near ciminate] and caccal sheat [Senimong bernoy); they can be a self-self-self-self-self-self-self-self-

	13:	[[[([(](acid aed []Lablic cleaveDic	USPAT; US-PGPUB; EPO; JPO; DERMENT	2003/06/11 17:2
-	8819	[[((2-methylademantyl adj methacrylate)]		
			USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/12 11:5
-	373305	photoresist ) sacm (mask)	USPAT; US-PGPUB; EPO; JPO; DERMENT	2003/06/12 13:3
-	44827	(pattern\$3 same (underlying) same (resist photoresist ) saem (mask)) same (conventional well-known well adj known)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/12 13:3
-	504	((pattern\$3 same (underlying) same (resist photoresist   saem (mask)) same (conventional well-known well adj known)) and (430/270,l,cels.)	USPAT; US-PGPUB; EPO; JPO; DERHENT	2003/06/12 13:36
-	374	(([pattern53 same (underlying) same (regist photoregist) same (mesh) same (conventional well-known well adj known) and (430/270.1.cels.)) and (semiconductor visi is nicrogatterning mircorfabrication)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/12 13:43
	276	(((pattern3) same (underlying) same (resist photoresist ) seem (mask) same (conventional well-known well adj known)) and (430/270.1.ccle.)) and (semiconductor VLSI ISI micropatterning mirrorrabpication)	USPAT	2003/06/12 13:43
-	1	(*6673511").PN,	USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/02/09 10:47
	5	((*20030232273") or (*6369181") or (*6013411")).PM.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/09 11:09
		(\$3-methyl adj sdamantyl adj sethacrylate)	USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/02/09 11:15
	17746	gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/09 11:16

		((\$3-methyladamantyl adj methacrylate)	USPATI	2004/02/09	
		(\$3-methyl ad) adamentyl adj methacrylate) ) and (gamma-butyrolactone \$6butyrolactone	US-PGPUB; EPO; JPO;	2004/02/09	11:
	6	butyrolactone "gamma"-butyrolactone ) ((\$3-methyladamantyl adj methacrylate)	DERWENT		
		(83-methyl adj adamantyl adj methacrylate)	US-PGPUB:	2004/02/09	11::
	!	) same (gamma-butyrolactone S6butyrolactone	EPO; JPO:		
		butyrolactone "gamma"-butyrolactone )	DERWENT		
-	1	(*6673511*).PN,	USPAT:	2004/02/16 :	14:
			US-PGPUB;		
			EPO; JPO; DERMENT	1	
	2674	acetal same lactone	USPAT:	2004/02/16 1	12.
			US-PGPUB;		
			EPO; JPO;		
	88	acetal same gamma-butyrolactone	DERWENT USPAT:		
		weeks out guiss - Ducyaotaceone	US-PGPUB:	2004/02/16 1	L3:
			BPO: JPO:		
			DERMENT		
	5	(("4996121") or ("6495310") or ("6387595") or ("6541183") or ("6660445")),pw.	USPAT	2004/02/16 3	13:
	362	benzyl same (acid adj labile)			
		benegi samo (acid ad) imbire)	USPAT; US-PGPUB;	2004/02/16 1	14:
			EPO: JPO:		
			DERWENT		
	246	(*6383713*).PN. (acetal adj moiety)	USPAT	2004/02/16 1	
	240	(acecus adj mosacy)	USPAT; US-PGPUB:	2004/02/16 1	٠7١
			EPO; JPO:		
			DERNENT		
	159212		USPAT;	2004/02/16 1	7:1
		cleav\$5)	US-PGPUB;		
			EPO; JPO; DERMENT		
1	17	((acetal adj moiety) ) same (acid nears	USPAT;	2004/02/16 1	
		(climinat\$3 remov\$3 labile cleav\$5))	US-PGPUB:	2004/02/16 1	713
			EPO, JPO,		
		20020150834.URPN.	DERMENT		
		VAMAMOTO-HAJIME	USPAT:	2004/02/16 1	
		YAMAMOTO-HAJIME-C-O-CANON-KABU	US-PGPUB:	2004/02/16 1	2:1
		YAMAMOTO-HAJIME-C-O-CANON-K-K	EPO: JPO:		
		YAMAMOTO-HAJIMU MURAKAMI-KENICHI	DERWENT	1	
1		MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU TAKECHI-SATOSHT			
		TAKECHI-SATOSHI-C-O-FUJITSU-LI			
	147	(yAMAMOTO-HAJIME	USPAT;	2004/02/16 1	
	- 1	YAMAMOTO-HAJIME-C-O-CANON-KABU	US-PGPUB:	2004/02/16 1	***
		YAMAMOTO-HAJIME-C-O-CANON-K-K	EPO; JPO;		
	i	YAMAMOTO-HAJIMU MURAKAMI-KENICHI	DERWENT		
	- 1	MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU TAKECHI-SATOSHI	1	1	
- 1		TAKECHI-SATOSHI-C-O-FUJITSU-LI ) AND (RESIST			
		PHOTORESIST)			
	20	((yAMAMOTO-HAJIME	USPAT;	2004/02/16 1	7,0
	1	YAMAMOTO-HAJIME-C-O-CANON-KAHU	US-PGPUB;		
		YAMAMOTO-HAJIME-C-O-CANON-K-K YAMAMOTO-HAJIMU MURAKAMI-KENICHI	EPO; JPO;		
i		MURAKAMI-KENICHIRO MURAKAMI-KENICHIROD	DERWENT		
		TAKECHI-SATOSHI			
		TAKECHI-SATOSHI-C-O-FUJITSU-LI ) AND (RESIST	1		
		PHOTORESIST!) AND ((ACID PHOTOACTD) NEAD			

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ENTER SCREEN EXPRESSION OR (SMD) end
 => screen 2067
       SCREEN CREATED
 Uploading C:\Program Files\Stmexp\Queries\09940665-2.str
        STRUCTURE UPLOADED
 -> que L2 AND L1
     QUE LS AND L1
 L3 HAS NO ANSWERS
                 SCR 2067
Structure attributes must be viewed using STN Express query preparation.
              QUE ABB=CN PLU=ON L2 AND L1
=> 8 13 550 8am
SAMPLE SEARCH INITIATED 13:40:45 FILE 'REGISTRY'
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SAMPLE SCREEN SEARCH COMPLETED -100.0% PROCESSED D ITERATIONS O AMSWORR

SEARCH TIME: 00.00.01 FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\* BATCH \*\*COMPLETE\*\* PROJECTED ITERATIONS:

0 SEA SSS SAM L2 AND L1

-> FIL CAPLUS, USPATFULL, HCAPLUS COST IN U.S. DOLLARS SINCE FILE ENTRY SESSION FULL ESTIMATED COST

TOTAL

FILE 'CAPLUS' ENTERED AT 13:40:50 ON 16 FEB 2004 USE IS SUBJECT TO THE TERMS OF YOUR SIN CUSTOMER ACRESMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 13:40:50 CM 16 PEB 2004 CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'NCAPLUS' ENTERED AT 13:40:50 CM 16 FEB 2004 USE IS SUBJECT TO THE TERMS OF YOUR STE CUSTOMER AGREEMENT. PLRASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

-> s 14 LS 0 14

PROJECTED AMENERS.

-> file req COST IN U.S. DOLLARS STRUCE FILM TOTAL SESSION 4.78

FULL ESTIMATED COST

PILE 'REGISTRY' SNYERED AT 13 41 10 ON 16 FEB 2004 USE IS SUBJECT TO THE TERMS OF YOUR SIN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS COPYRIGHT (C) 2004 American Chemical Society (ACS)

Property values tagged with IC are from the BIC/VINITI data file provided by Infechen

STRUCTURE FILE UPDATES: 15 FEB 2004 HIGHEST RN 650577-28-9 DICTIONARY FILE UPDATES: 15 FEB 2004 HIGHEST RN 650577-28-9

TSCA INFORMATION NOW CURRENT THROUGH JULY 14, 2003

please note that search-term pricing does apply when conducting SwartSELECT searches.

Crossover limits have been increased. See MMLP CROSSOVER for details. Experimental and calculated property data are now available. For more information enter HELP PROP at an arrow prompt in the file or refer to the file surmary about on the web at: http://www.cas.org/ONLINE/DESS/registryss.html

=> .....Testing the current file ... screen ENTER SCREEN EXPRESSION OR (END) | end

-> acreen 2067

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STRUCTURE UPLOADED

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QUE LT AND L6

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Structure attributes must be viewed using STN Express query preparation. - QUE ABB-ON PLU-ON L7 AND L6

668

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-> s 18 sas sam SAMPLE SEARCH INITIATED 13:42:51 FILE 'REGISTRY' SAMPLE SCREEN SEARCH COMPLETED -20 TO ITERATE

100.0% PROCESSED 20 ITERATIONS SBARCH TIME, 00 00.01

1 AMENERS

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETR\*\* \*\*COMPLETE\*\* PROJECTED ITERATIONS: 132 TO

PROJECTED ANSWERS 1 70

L9 1 SEA SSS SAM L7 AND L6 THE LOUISE SHOTALL, HAVING SINCE FIRE COURSE OF THE COURSE

FILE 'ECAPLUS' ENTERED AT 13:42:57 OK 16 FEB 2004
USE IS SUBJECT TO THE TERMS OF YOUR SIN CUSTOMER AGREEMENT.
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-> 5 19

=> duplicates remove 110
DUPLICATE PREFERENCE IS "CAPLUS, USPATFULL, HCAPLUS"
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(m):m

PROCESSING COMPLETED FOR L10
L11 3 DUPLICATE REMOVE L10 (2 DUPLICATES REMOVED)

=> d 111 1-3 ibih hitstr

LAI AMSWER 1 OF 3 USPATFULL on STN

ACCESSION NUMBER: 91:17029 USPATFULL

ITLE. Electrophotographic lithographic printing plate procursor containing resin having bydroxy group forming

INVENTOR(S) Elichi, Shizuoka, Japan Ishii, Kazuo, Shizuoka, Japan

PATENT ASSIGNES(S) Fuji Photo Film Co., Ltd., Kanagawa, Japan (non-U.S. corporation)

PATENT INFORMATION: US 4996121 19910226

APPLICATION INFO.: US 1989 203400 19800104 (7)

PRIORITY INFORMATION: JP 1988-265 19880106
JP 1988-14577 19880127
DOCUMENT TYPE: Utility
FILE SECRET! Granted

PRIMARY EXAMINER McCanish, Marion C.
ASSISTANT EXAMINER ROBE, Christopher D.
Sughrue, Nion, Zinn, Macpeak & Seas

NUMBER OF CLAIMS: 10
EXEMPLARY CLAIM: 1
LINE COUNT: 1200

CAS INDEXING IS AVAILABLE FOR THIS PATENT. 17 124660-88-4

(electrophotog, plate with photoconductive layer containing, for lithogplate fabrication)

lates randomness.

124560-28-4 UEPATFULL

2-Propensic acid, 2-methyl-, athyl ester, polymer with 4-hydroxybatyl

2-methyl-2 propensate and 2-[[tetrahydro-2-furanyl]oxy]athyl

2 methyl-2-propenoate (9CI) (CA INDEX NAME) CM 1

CRN 121462 74-6 CMF C10 H16 04

0-CH2-CH2-0-C-C-No

CW

CRN 997-46-6 CMF C8 814 03

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0 GH2
 NO- (CH2) 4-0-C-C-He
        CN 3
        CHH 97-63-2
       CMF C6 N10 02
   Hag o
LA1 AMENUER 2 OF 3 CAPLUS COPYRIGHT 2004 ACS ON STN DUPLICATE 1
ACCESSION NUMBERS:
                                 1990:468420 CAPLUS
DOCUMENT NUMBER
                                  113:68420
TITLE:
                                 Direct-imaging lithographic original plate having 
image-receiving layer with binder containing protected
                                 hydroxy-substituted polymer and hardener
INVENTOR(S)
                                 Nato, Biichi; Ishii, Kazuo
Fuji Photo Film Co., Ltd., Japan
Jpn. Kokai Tokkyo Koho, 13 pp.
PATENT ASSIGNRE(S):
SOURCE
                                 CODEN: JKXXAP
DOCUMENT TYPE
                                 Patent
LANGUAGE:
                                 Japanese
FAMILY ACC. NUM COUNT:
PATERT INFORMATION:
      PATENT NO. | KIND DATE
JP 01271292 A2 19891030
                                                        APPLICATION NO DATE
                                                        JP 1988-100192 19880425
PRIORITY APPLN: IMPO.;
                                                     JP 1988-100192
                                                                              19880425
     124660-88-4
      RL: USES (Uses)
          (bander, for image-receiving layer, for direct-imaging lithog. plate,
hydrophilicity associated with oil-based ink affinity in
     124660-88-4 CAPLUS
     12480/tora CHANGE
2-Propanoic acid, 2-mathyl-, ethyl ester, polymar with 4-hydroxybutyl
2-methyl-2-propanoate and 2-[(cerxahydro-3-furanyl)oxylethyl
2-methyl-2-propanoate (9CI) [CA. HOMEK MANGE)
      CN 1
      CRN 121462-74-6
     CMF C10 H16 04
```

0-сн2-си2-о-с-с-и

CME 997-46-6
CMF C8 H14 03

ENG (CM<sub>2</sub>) 4-0-C-C-Me

CM 3
CMX 57-63-2
CMF C6 H10 02

H2C 0
HA=C-C-OSE

L11 AMSWER 3 OF 3 CAPLUS COPYRIGHT 2004 ACS ON SYN DUPLICATE 2 ACCESSION NUMBER: DOCUMENT NUMBER TITLE: Electrophotographic lithographic printing plate INVENTOR(s) Puji Pkoto Film Co., Ltd., Japan Eur. Pat. Appl., 43 pp. CODEN: EPXXDW PATENT ASSIGNED(S): SOURCE: DOCUMENT TYPE: Patent LANGUAGE: PARKLY ACC. NUM. COUNT: PATENT INFORMATION: PAYENT NO KIND DATE APPLICATION NO. DATE EP 323854 2.2 19890712 EP 1989-100179 19890105 EP 323854 19910703 R: DE GR 3.2 19890717 JP 1988-265 19880106 A2 19890801 JP 1988-14577 19880127 19910226 US 1989-293400 19890104 PRIORITY APPLN. INFO.: JP 1988-265 19880106 JP 1988-14577 19880127 124660-88-4 RL: USES (Uses)

RL: USRS (Uses) (electrophotog, plate with photoconductive layer containing, for lithog, plate fabrication)

l4660-Bs-(ANDLUS 2-Propencie acid, 2-methyl-, athyl ester, polymer with 4-hydroxybutyl 2-methyl-2-propencate and 2-{(tetrahydro-2-furamyl)oxylethyl 2-methyl-2-propencate (9Cf) (CA lBDEX MEMS)

CRN 121462-74-6 CNF CLO N16 04

О - CH2 - CH2 - O - C - C - Me

CN 2 CRM 997-46-6 CMF CN 914 03

O CH2

BO (CN<sub>2</sub>)<sub>4</sub> O C C N<sub>0</sub>

CN 3

CNN 97-63-2

CNY 06 H10 02

H<sub>2</sub>C 0

FULL SSTIMATED COST 15.14 21.18

FILE "RECISTRY" ENTERED AT 13:43:52 ON 16 FEB 2004 USB IS SUBJECT TO THE TERMS OF YOUR STM CUSTOMER AGREGMENT. PLEASE EST WELLP URAGETERMS" FOR DETAILS. COPYRIGHT (C) 2004 American Chemical Society (ACS)

Property values tagged with IC are from the ZIC/VINITI data file provided by Informer

STRUCTURE PILE UPDATES: 15 PEB 2004 HIGHEST RN 650577-28-9 DICYTORURY FILE UPDATES: 15 PEB 2004 HIGHEST RN 650577-28-9

TSCA INFORMATION NOW CURRENT THROUGH JULY 14, 2003 Please note that search-term pricing does apply when

conducting Smartestate pering over apply when conducting Smartestate pering over apply when Crossover limits have been increased. See HELD CROSSOVER for details.

Experimental and calculated property data are now available. For more information enter HELD FROP at an arrow prompt in the file or refer to the file summarry sheet on the web at:

http://www.cas.org/ONLINE/DESS/registryss.html -> ....Testing the current file.... screen

SEFFER SCREEN EXPRESSION OR (END) | end

=> screen 2067

L12 SCREEN CREATED

Uploading C \Program Files\Stnerp\Queries\09940665-4.str

L13 STRUCTURE UPLOADED

-> Que L13 AND L12

L14 QUE L13 AND L12

114 HAS NO ANSWERS 112 SCR 2067 113 STR

=> d

Structure attributes must be viewed using STN Express query preparation. L14 QUE ASS-ON PLUSON L13 AND L12

50 ANSWERS

-> S 214 SES SON SAMPLE SCREEN SEARCH COMPLETED - 8008 TO ITERATE SAMPLE SCREEN SEARCH COMPLETED - 8008 TO ITERATE

12 5% PROCESSED 1000 FTERATIONS INCOMPLETE SEARCH (SYSTEM LIMIT EXCHEDSE)

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*
BATCH \*\*COMPLETE\*\*

PROJECTED ITERATIONS: 154798 TO 165522
PROJECTED AMENUERS: 64257 TO 71237

L15 50 SEA SSS SAM 113 AND 112

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  -> d
  LIS HAS NO AMENERS
                   SCR 2067
                                _26
                    1 - 20
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                 QUE ABB-ON PLU-ON L17 AND L16
 -> = 118 pps sam
 SAMPLE SEARCH INITIATED 13:45:58 FILE 'REGISTRY'
 SAMPLE SCREEN SEARCH COMPLETED - 8719 TO ITERATE
  11.5% PROCESSED
                      1000 ITERATIONS
                                                                    SO AMENERS
 INCOMPLETE SEARCH (SYSTEM LIMIT EXCERDED)
 SHARCH TIME: 00.00.01
 FULL FILE PROJECTIONS: ONLINE **COMPLETE**
                          BATCH **COMPLETE**
 PROJECTED ITERATIONS
                               168786 TO 179974
 PROJECTED ANSWERS:
                                62982 70
                                            69894
              50 SEA SSS SAM L17 AND L16
 => FIL CAPLUS, USPATFULL, MCAPLUS
 COST IN U.S. DOLLARS
                                                      SINCE FILE
                                                                      TOTAL
                                                            ENTRY
                                                                    SESSION
 FULL ESTIMATED COST
                                                            1.68
FILE 'CAPLUS' ENTERED AT 13:46:03 ON 16 FEB 2004
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT
PLEASE SER WHILP USUSDETENS' FOR DETAILS.
COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)
FILE 'USPATFULL' SWIERED AT 13:46:03 ON 16 FEB 2004
CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)
FILE 'HCAPLUS' SMITSRED AT 13,46,03 ON 16 FRE 2004
FILE HOGHELS' MELEKEL AL ASSESSED OF THE TERMS OF YOUR SIN CUSTOMER AGREEMENT,
PLEASE SEE "HELD USAGETERMS" FOR DETAILS,
COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)
=> 2 119
            106 L19
-> s 120 and (resist or photoremist)
121
             5 L20 AND (RESIST OR PHOTORESIST)
-> duplicates remove 121
DUPLICATE PREFERENCE IS 'CAPLUS, USPATFULL, HCAPLUS'
KERP DUPLICATES FROM MORE THAN ONE PILE? Y/(X):E
PROCESSING COMPLETED FOR L21
               2 DUPLICATE REMOVE L21 (3 DUPLICATES REMOVED)
=> d 122 1-2 ibib hitstr
LT2 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 1
ACCESSION NUMBER
                          2002;556013 CAPLUS
DOCUMENT NUMBER -
                          137:116960
TITLE
                          Lithographic plate having conformal overcost and
                           photosensitive layer on a rough substrate
```

Teng, Gary Ganghui

USA

PATENT ASSIGNER(S):

SCREEN CREATED

```
SOURCE
                           U.S. Pat. Appl. Publ., 10 pp., Cont.-in-part of U.S.
                           Ser. No. 873,598.
                           CODEM DEXXOD
  DOCUMENT TYPE
                           Patent
  LANGUAGE:
  FAMILY ACC. NUM. COURT. 8
  PATENT INFORMATION:
       PATERT NO.
                      KIND DATE
                                             APPLICATION NO. DATE
       UR 2002098447
                         3.1
                              20020725
                                             UE 2002-46789
                                                               20020115
                         22
                              20021217
       US 6387595
                         Bl
                              20020514
                                             US 2000-699784
                                                               20001030
                        0.1
                              20030220
                                             US 2001-873598
                                                              20010604
       US 6541183
                         B2
                            20030401
 PRICRITY APPLN. IMPO
                                          US 2000-699784 A2 20001030
US 2001-873598 A2 20010604
      443150-29-6P, Ebecryl RX 8301-Sartomer SR 399 copolymer
      RI, SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
          (photosensitive layer of lithog, printing plate containing)
 BN
      443150-29-6 CAPLAIS
      2-Propencic acid, 2-[[3-hydroxy-2,2-bis][[1-oxo-2-
      propenyl) oxylmethyl]propoxylmethyl]-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3-
      propagedlyl ester, polymer with Mbeoryl RX 8301 (9CI) (CA INDEX NAME)
      СМ
      CRN 344346-13-0
           Unspecified
      CCT PNS, MAN
 *** STRUCTURE DIAGRAM IS NOT AVAILABLE ***
      CRN 60506-81-2
      CMF C25 H32 012
H2C=CH-C-O-CH2-C-CH2-O-CH2-C-CH2-O-C-CH2-O-C-CH
L22 AMSKER 2 OF 2 CAPLOS COPYRIGHT 2004 ACS on STN DUPLICATE 2
ACCESSION NUMBER:
                         2002:429450 CAPLUS
DOCUMENT NUMBER:
                         137:13269
                          Photosensitive composition for lithog, printing plate
INVESTOR (S):
                         Pujita, Kazuo, Tan, Shiro
PATENT ASSIGNEE (S):
                         Puji Photo Film Co., Ltd., Japan
U.S. Pat. Appl. Publ., 20 pp.
                         CODEN: USKKCO
DOCUMENT TYPE.
                         Patent
LANGUAGE
                         English
FAMILY ACC: NUM: COUNT: 2
PATENT INFORMATION.
     PATHNT NO.
                      KIND DATE
                                           APPLICATION NO. DATE
     US 2002068235
                       8.1
                            20020606
                                            US 2001-970988
                                                             20011005
     US 6660445
                            20031209
     JP 2002122989
                       A2
                                            JP 2000-312929
                                                              20001013
     CN 1355448
                            20020626
                                           CN 2000-133306
                                                              20001123
                            20020918
                                            JP 2001-69062
    CN 1349132
                                                             20010312
                            20020515
                                            CN 2001-139305
                                                             20011013
PRICETTY APPLE INFO :
                                        JP 2000-312929 A 20001013
                                        JP 2001-69062
                                                        A 20010312
    410100-32-27
    RL: PRP (Properties), SPN (Synthetic preparation); TEM (Technical or
    angineered material use); PREP (Preparation); USES (Uses)
       (photosensitive composition for lithog: printing plate containing
    410100-32-2 CAPLUS
    2-Propenoic acid, 2-methyl-, 2-(2-methoxyethoxy)ethyl ester, polymer with
    4-ethenyl-N-(phenylsulfonyl)benzenesulfonamide and methyl 2-propenoate
     (9CI) (CA IMPRE NAME)
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CS

CM 1 CRN 47121-58-4 CMF C14 H13 N D4 82

Pin S NB S CB CB2

CRN 45103-58-0 CRN C9 H16 04

""| || |-C-C-O-CH2-CH2-O-CH2-CH2-ONE

CN 3

CHM 96-33-3 CMF C4 H6 02

MeO-C-CH== CH2